

Literature

Physics of Semiconductor Devices

S.M. Sze, Kwok K. Ng

Available as eBook on

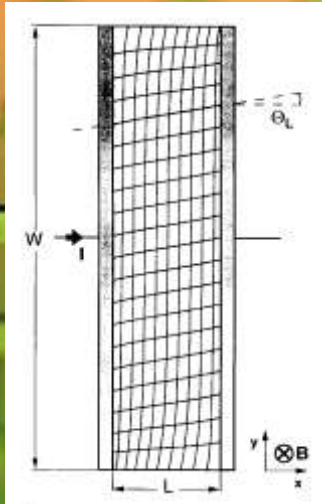
<http://www.lub.lu.se/en/search/lubsearch.html>

This lecture chapters 14.4
Magnetic Sensors

Magnetic sensors

- Digital Compass
- Current sensor
- Position, acceleration
- Rotational velocity
- Flow (Ferrofluids)
- Biosensors (antibody labeled microbeads)

Lorentz deviation - magnetoresistans -

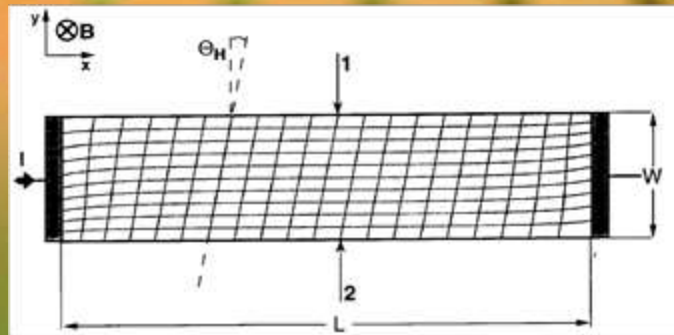


Lorentz force: $\mathbf{F} = -q\mathbf{v} \times \mathbf{B}$

$$(\rho_{nB} - \rho_n) / \rho_n = (r_n \mu_n B)^2$$

magnetoresistive effect small for silicon
ex. $\rho_{nB} \approx 1.02 \rho_n$ at $B = 1$ Tesla

Hall effect



$$V_H = V_1 - V_2 = R_H \frac{IB}{t}$$

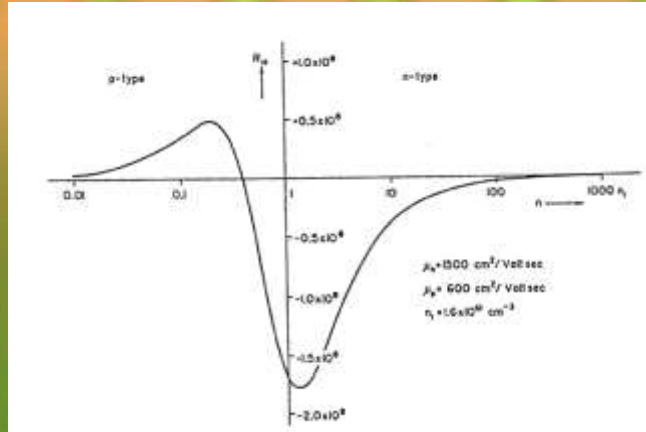
Hall coefficient: $R_H = -r_n / qn$

Where r_n electron deflection coefficient
and n density of free electrons (holes).

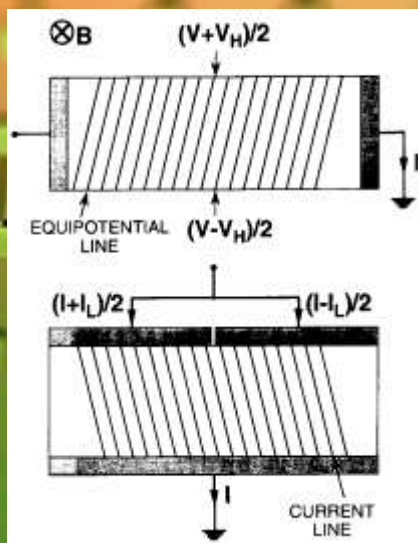
Low dopant levels yields high Hall coefficient;

Relative coefficient of sensitivity is: $R_H / t = V_H / IB$

Hall coefficient for semiconductors



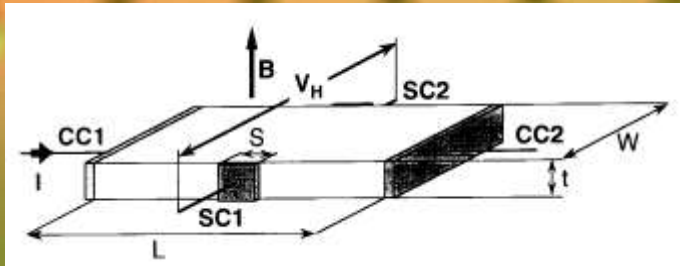
Operative modes for Hallelement



Hall voltage mode

Lorentz current mode

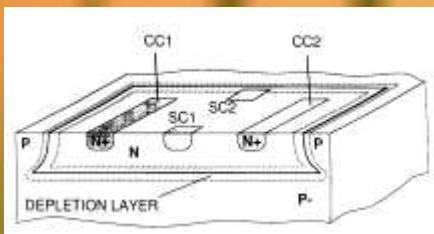
Hall element



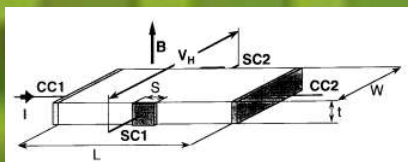
- CC1 = current contact 1
- CC2 = current contact 2
- SC1 = sensor contact 1
- SC2 = sensor contact 2

Relative sensitivity factor: $R_H/t = V_H/IB$

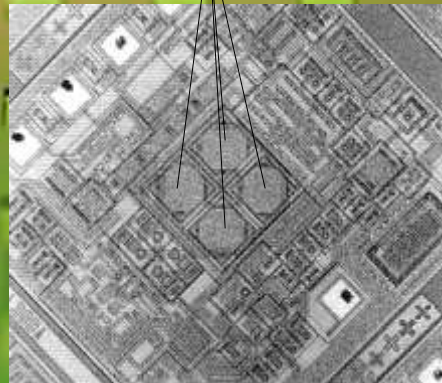
Silicon integrated Hallelement -Vertical sensitivity-



Jfr.

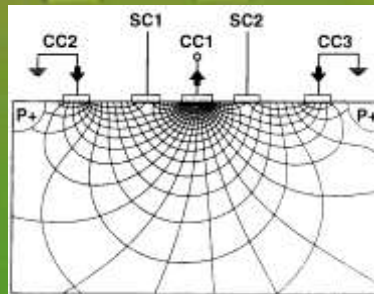
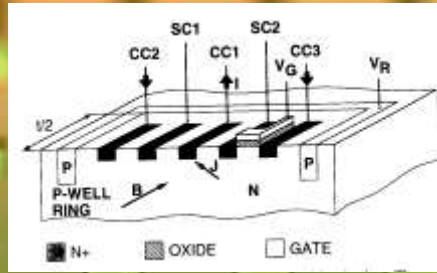


Hallelement



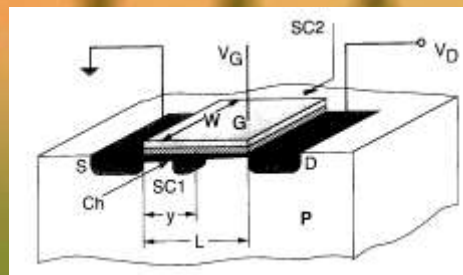
Vertical Hall Device - VHD

-Horizontal sensitivity

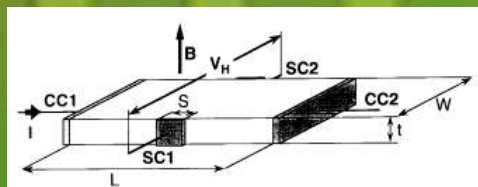


Popovic 1984

Hall MAGFET



J_{fr}.



- Higher sensitivity
- Faster
- Smaller

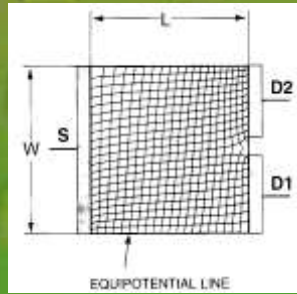
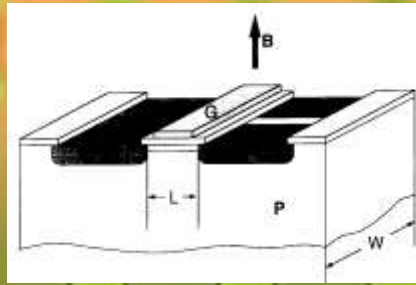
$$V_H = G I_D B r_{nch} / Q_{ch}$$

$$V_H = -I B r_n / qnt;$$

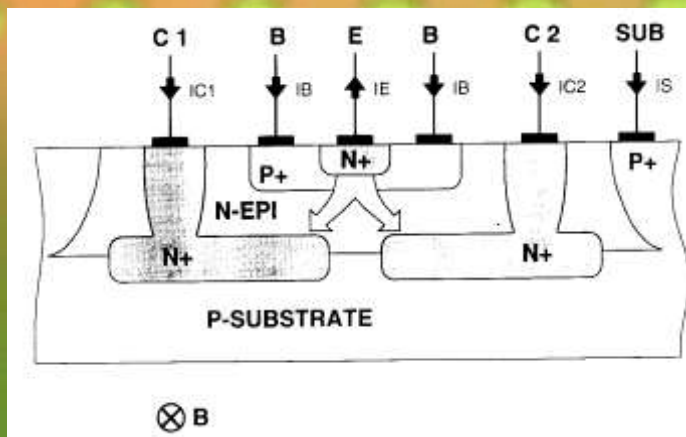
$$S_I = r_{nch} / Q_{ch} =$$

$$r_{nch} / (V_G - V_T)$$

Dual drain MAGFET



Dual collector vertical magnetotransistor



$$I_{C1} - I_{C2} = G r_n \mu_n (L/W_E) I_{C0} B$$

Optical Sensors

- Heat
- IR
- Position
- Velocity (Rotational velocity)
- Flow
- Chemical Sensors
 - Absorbance
 - Luminescence

Literature

Physics of Semiconductor Devices

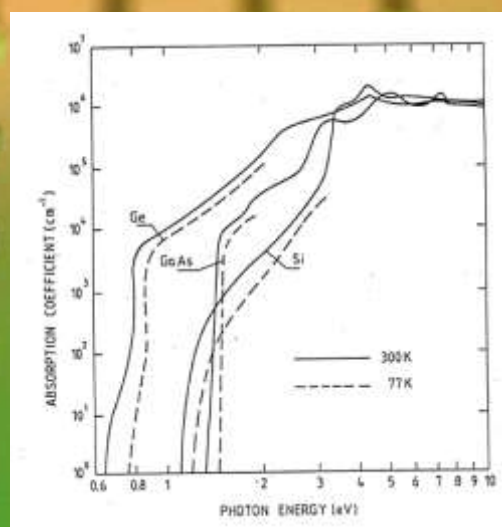
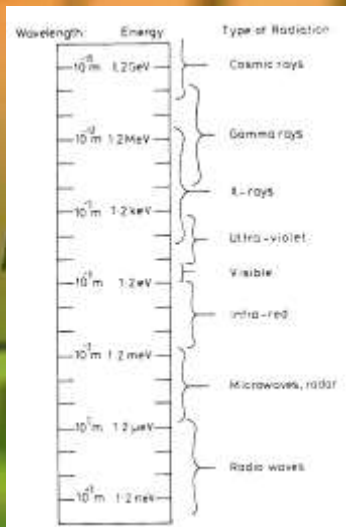
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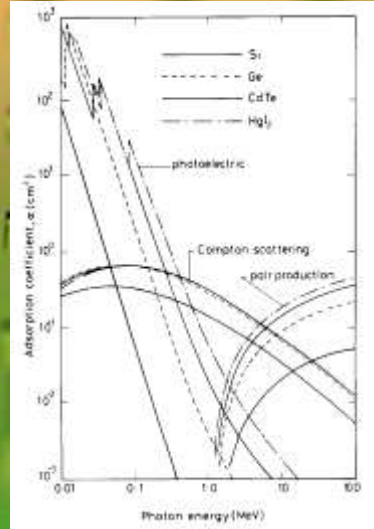
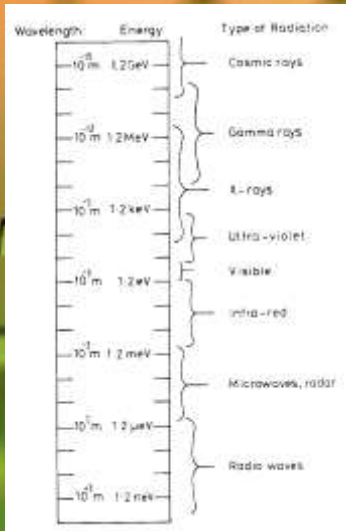
<http://www.lub.lu.se/en/search/lubsearch.html>

This lecture chapters 13.2-5
Photodetectors

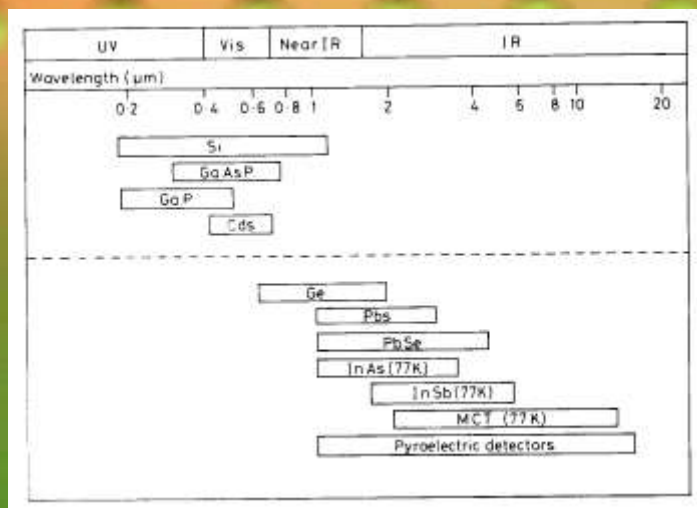
Absorption coefficient of radiation in semiconductors



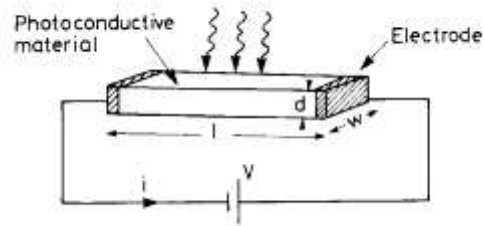
Absorption coefficient of radiation in semiconductors



Usable wavelengths for semiconductor based optical sensors



Photoconductive cell



$$R = l/(\sigma dw)$$

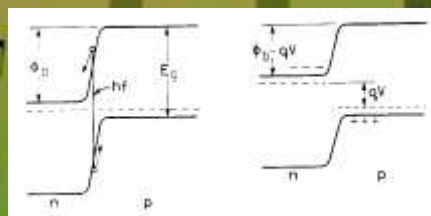
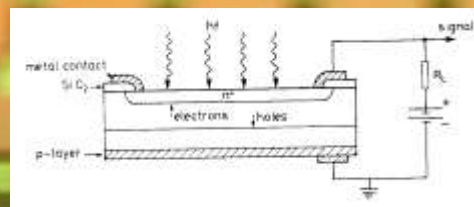
$$\Delta\sigma = eN_t(\mu_n\tau_n + \mu_p\tau_p)$$

μ is the mobility for holes (p) resp. electrons (n) and τ is particle mean lifetime.

N_t is the number of charge carriers generated per second:

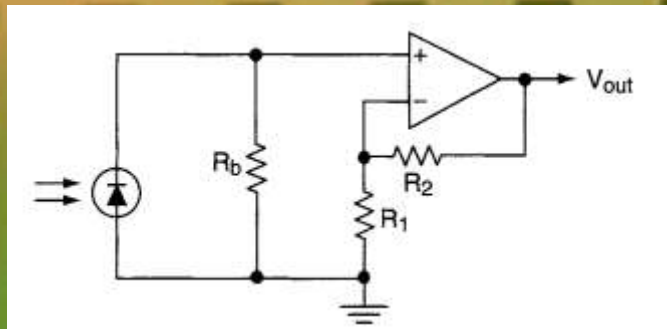
$$N_t = \eta\Phi(1 - e^{-\alpha d})$$

Photo diode



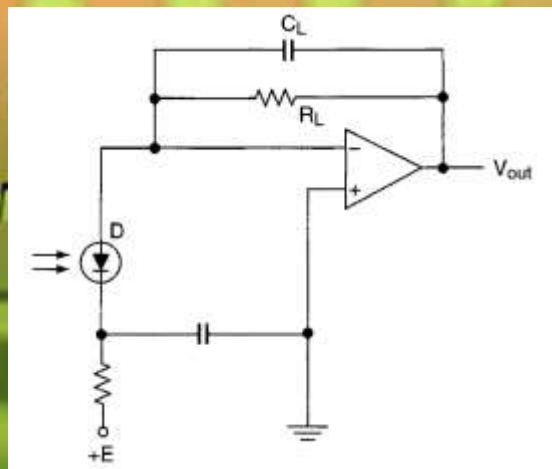
Electron-/hole pairs formed in the intrinsic region of the reversed potential pn-junction generates the photocurrent.

Photovoltaic mode

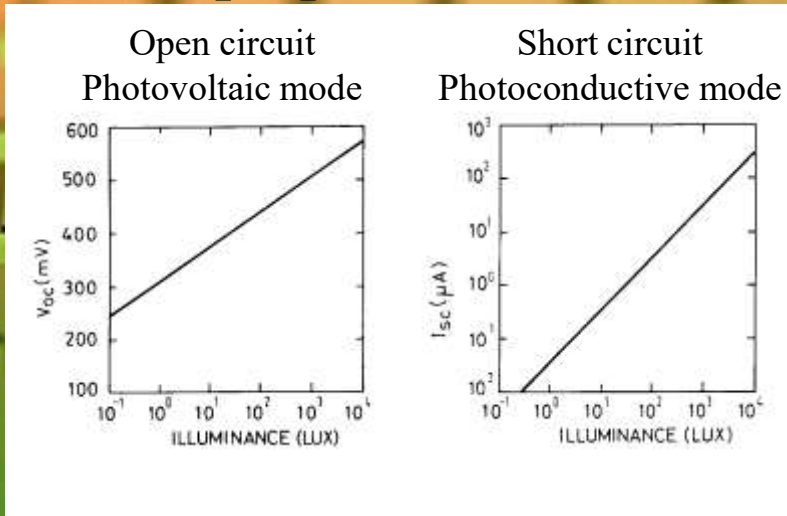


$$V_{oc} = \frac{kT}{q} \ln\left(\frac{I_L}{I_S} + 1\right)$$

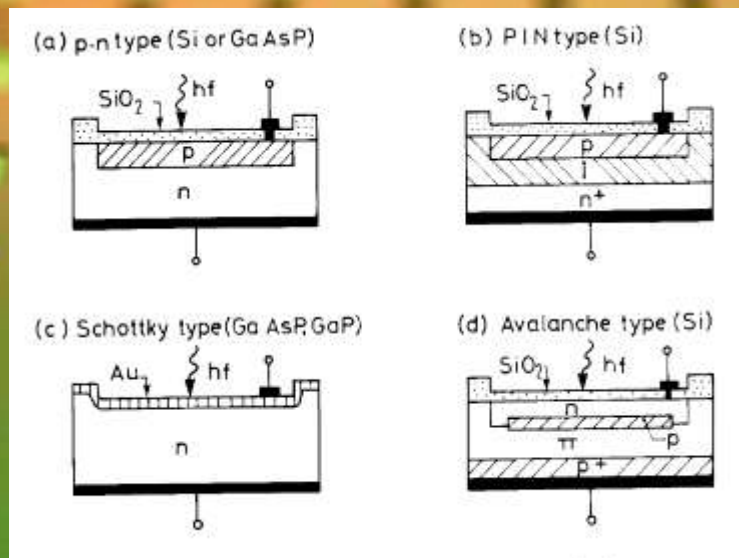
Photoconductive mode



Characteristics of pn-photodiode



Variations of the photodiode



Advantages of the photodiode compared to the photoconductive cell

- * higher sensitivity
- * faster
- * smaller
- * more stable
- * better linearity

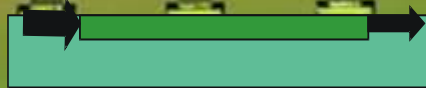
Waveguides

Free-space optics versus integrated optics

a) Free-space optics



b) Integrated optics

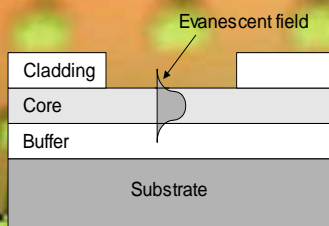


- Increased optical path length. Lambert-Beers law:

$$A = abc \text{ (molar absorptivity, path length, concentration)}$$

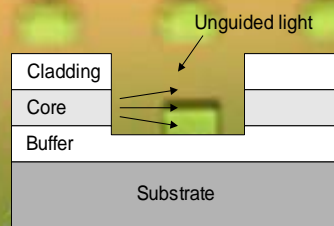
- Rugged and alignment-free operation of the devices

Detector configurations



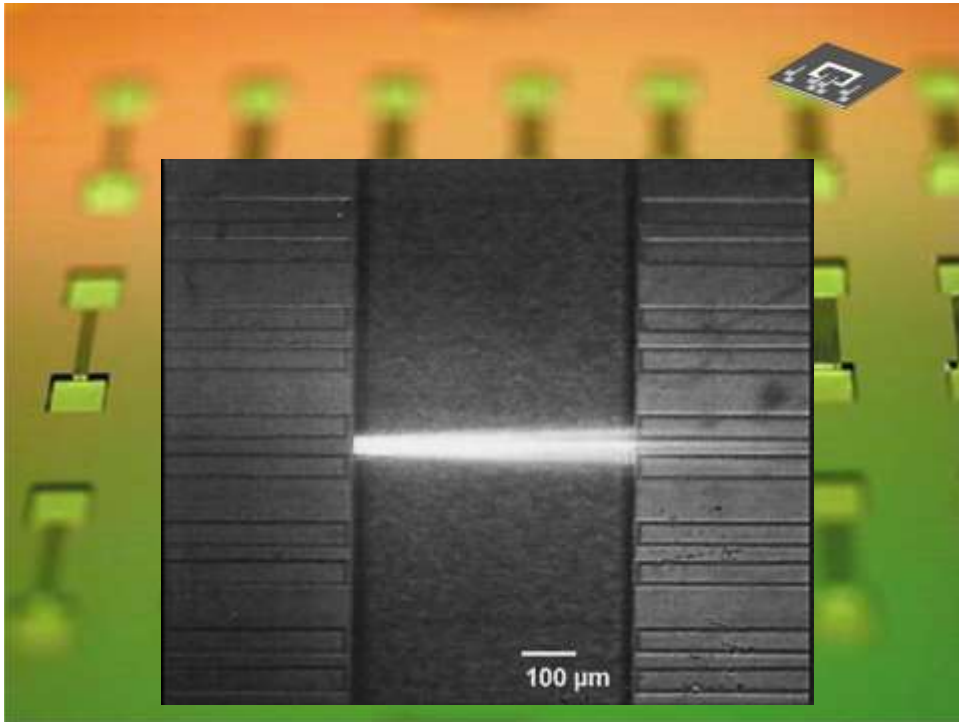
Evanescent wave sensing

- Probes the surface of the core layer
- Light is guided in the detection region

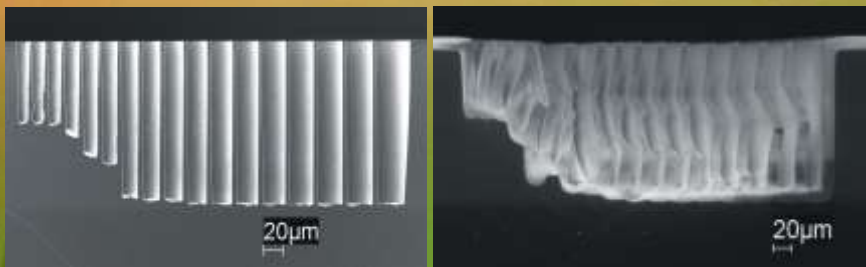


Free-space wave sensing

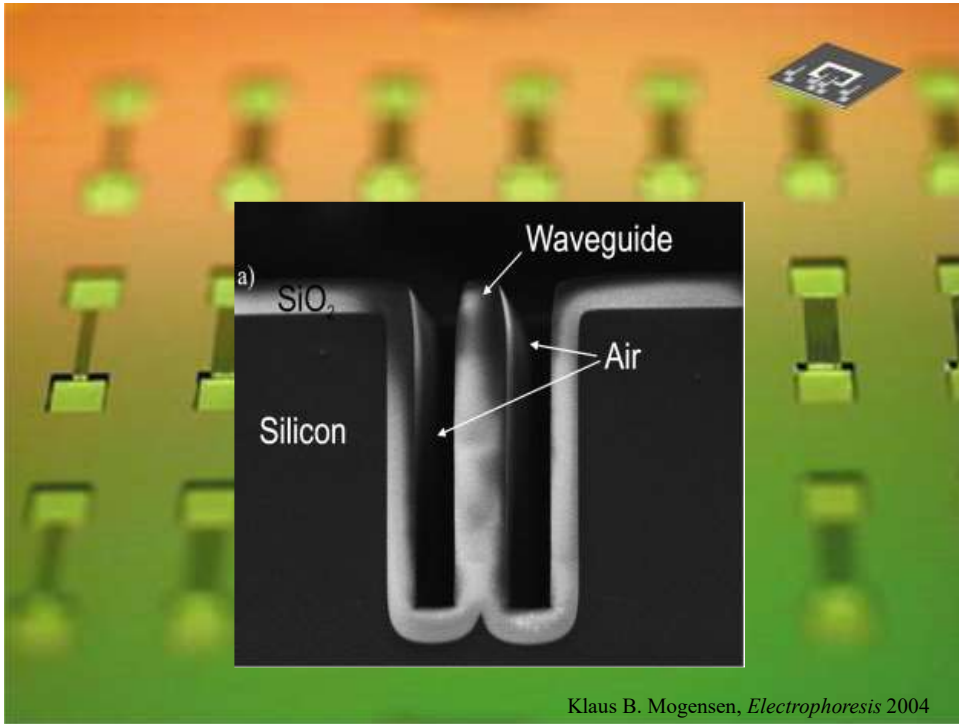
- Probes the bulk of the solution
- Light is unguided in the detection region



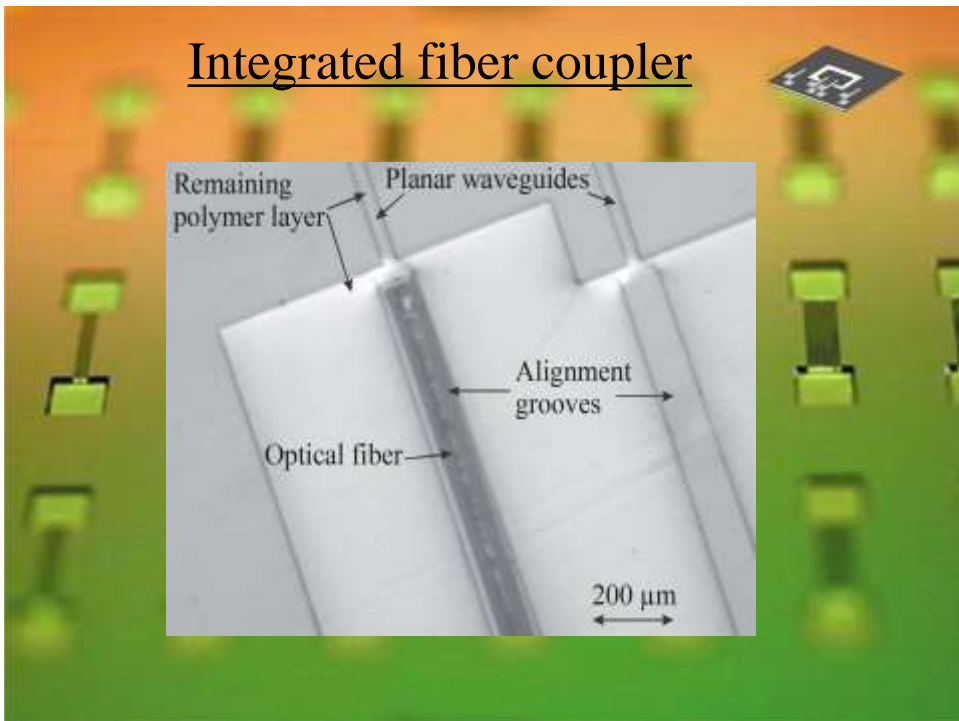
High-aspect ratio electrically insulated channels



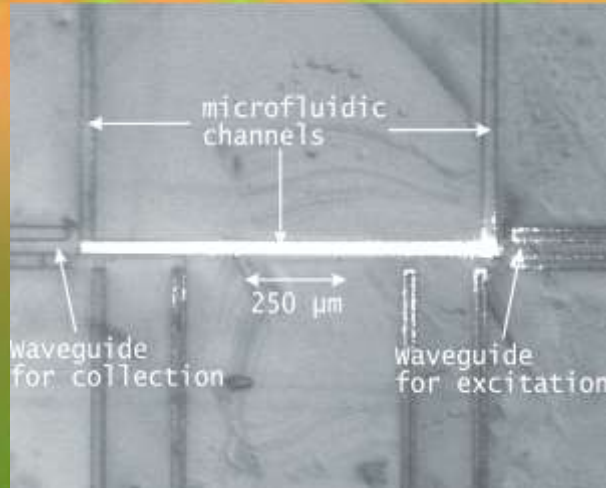
- Anisotropic KOH etching of $\langle 110 \rangle$ silicon
- Thermal oxidation of silicon channels walls



Klaus B. Mogensen, *Electrophoresis* 2004

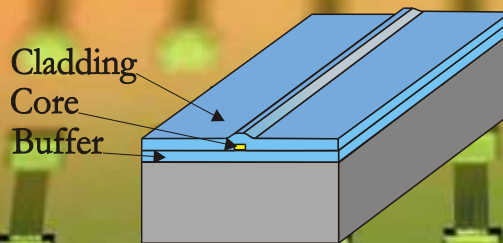


Chemical absorbance cell



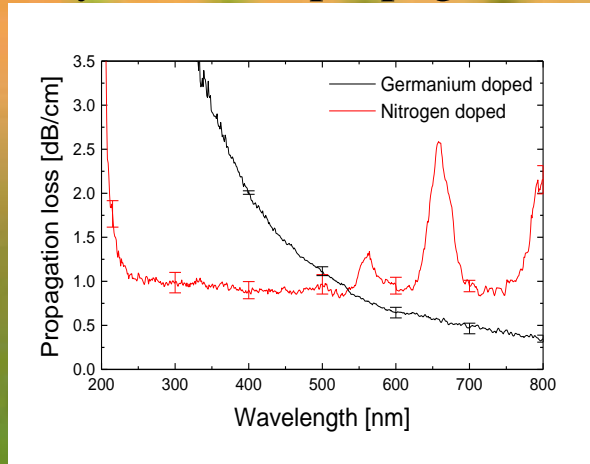
- 1000 μm absorbance length
- 30 μm channel width

Fabricated multimode waveguides



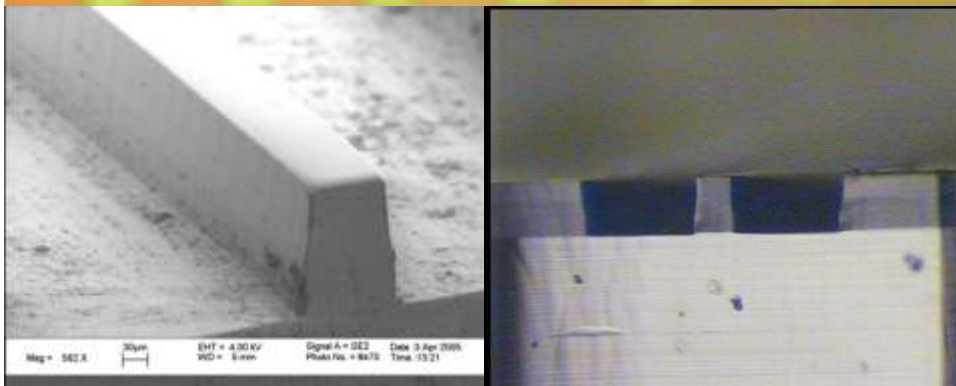
Width: 24 μm	Nitrogen doped	Germanium doped
Buffer	10 μm wet oxide	10 μm wet oxide
Core	4 μm SiO_xN_y	4 μm SiGe_xO_y
Cladding	7 μm SiO_x	5 μm BPSG

Spectrally resolved propagation loss



- Calculated with cut-back method with 5 different lengths

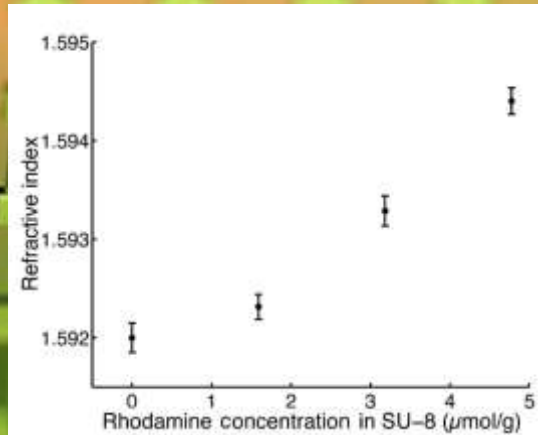
Polymer waveguides



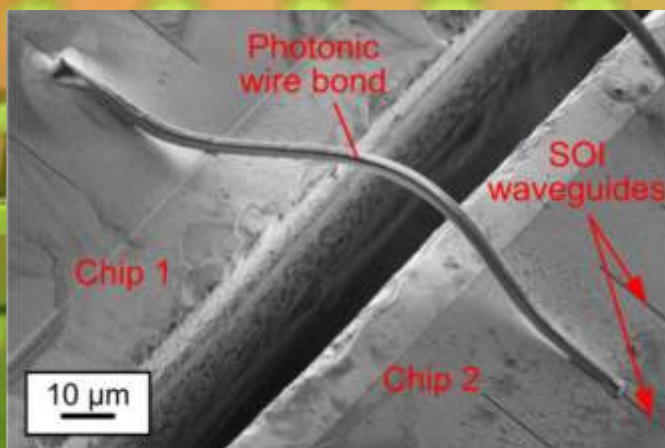
- Spin-coated or thermally bonded thin films with different refractive index
- Structured with lithography or milling

Bundgaard & Geshke 2006

Polymer waveguides



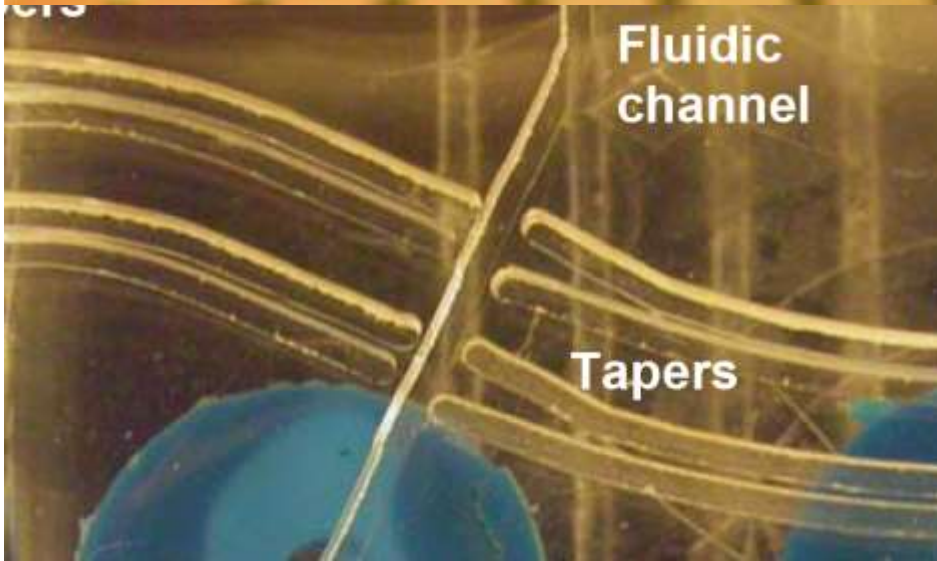
Optical wire bond



- 3D printed optical waveguide chip-to-chip optical interconnect

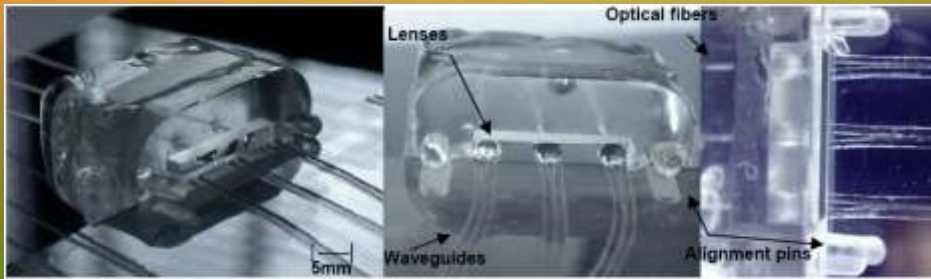
N. Lindenmann et al. 2011

Tapers



Perozzelli, 2005

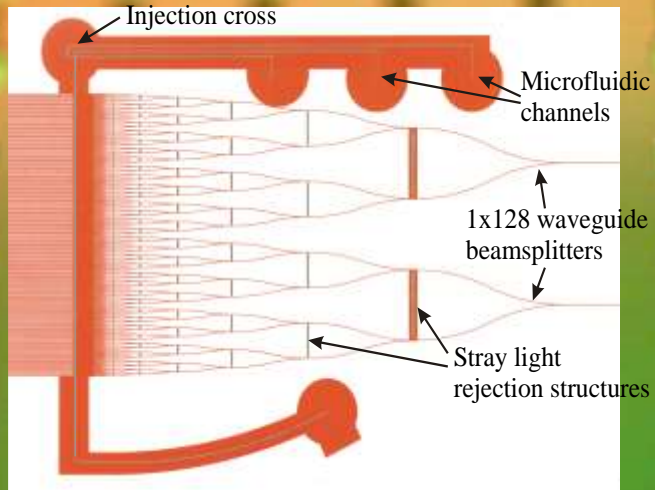
Lenses



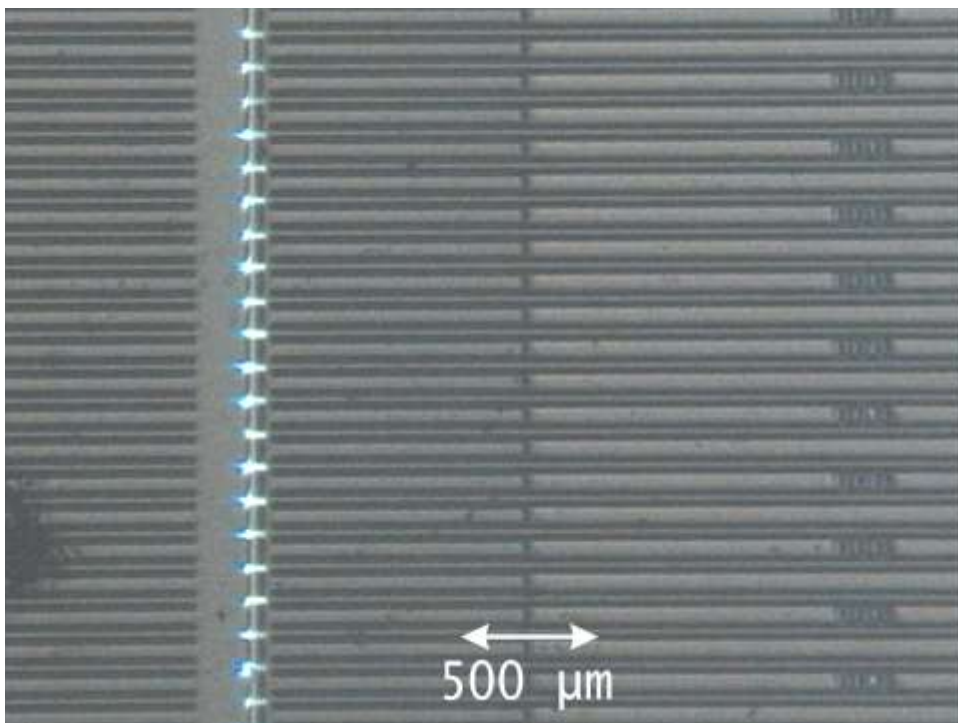
Spherical lenses in PDMS
moulded from isotropically etched silicon

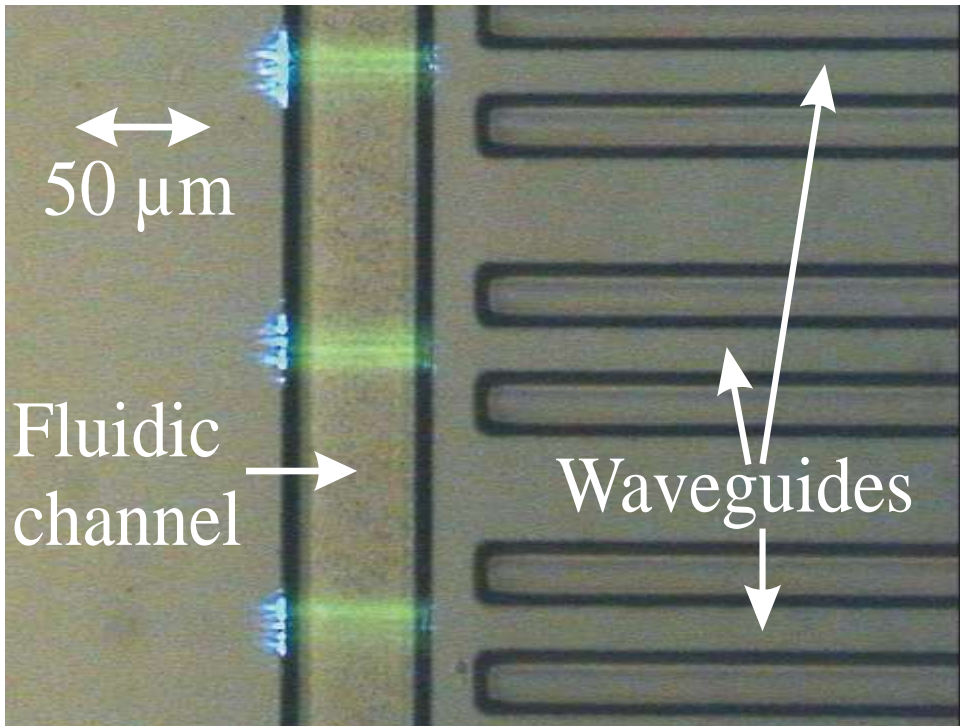
Perozzelli, 2005

Mask design

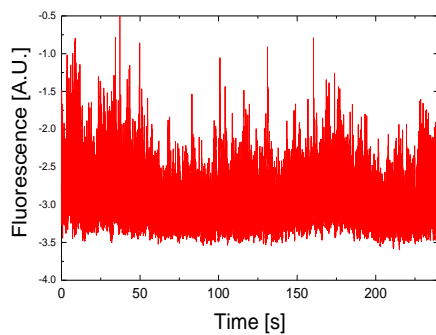


Klaus B. Mogensen, 2004



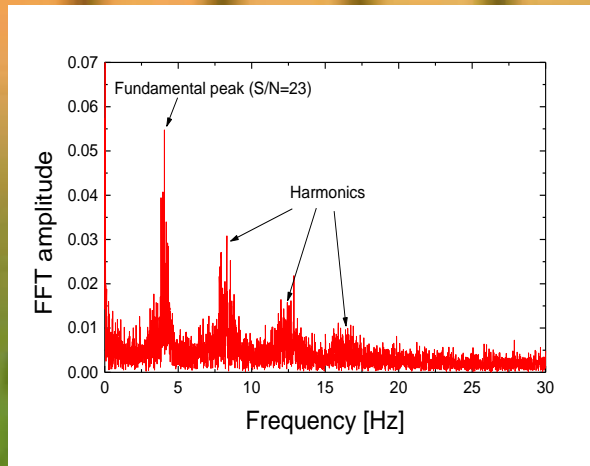


Particle velocity measurements



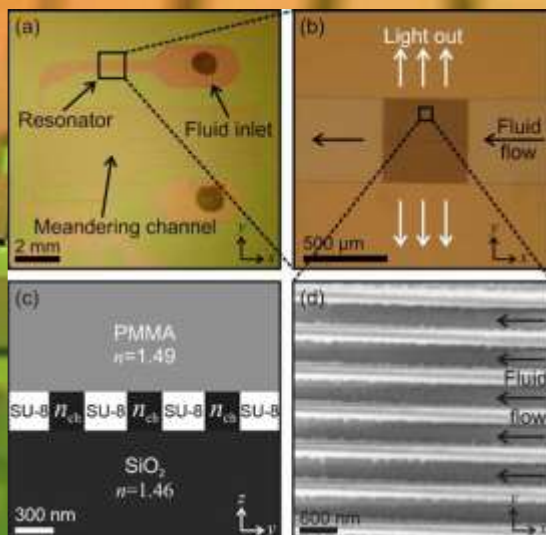
- $1.0\ \mu\text{m}$ fluorescent beads (1,000 fold dilution in 0.1x TBE)
- Field strength: 111 V/cm

Fourier transformation



- Fundamental peak at 4.1 ± 0.5 Hz (410 ± 50 $\mu\text{m/s}$)

Laser-on-chip



Dye laser
(Rhodamine 6G)

Laser light is
formed in a Bragg
resonator (b)

Pumped with
external 532 nm
Nd:YAG laser

Gersborg-Hansen and Kristensen, 2006

Laser-on-chip

